

Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 251475US3DIV		SERIAL NO. New Application	
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT Kousaku MATSUNO, et al.			
				FILING DATE Herewith		GROUP	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
<i>MK</i>	AA	6,080,531	06/27/00	Carter et al.			
	AB	5,971,368	10/26/99	Nelson et al.			
	AC	5,983,909	11-1999	Yeol et al.			
	AD	6,920,777	09-2001	Imaoka et al.			
	AE	6,325,359	12-2001	Haga et al.			
	AF	5,503,708	04-1996	Koizumi et al.			
	AG	6,086,057	07-2000	Mitsumori et al.			
	AH	6,039,815	03-2000	Yeol et al.			
	AI	6,035,871	03-2000	Eui-Yeol, Oh			
	AJ	4,812,201	03-1989	Sakai et al.			
	AK	5,783,790	07-1998	Mitsumori et al.			
	AL	6,217,665	04-2001	Suzuki			
<i>MK</i>	AM	5,739,575	04-1998	Numano et al.			
	AN						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION		
					YES	NO	
<i>MK</i>	AO	8-78372	03-1996	Japan (w/ abstract)		xx	
<i>MK</i>	AP	63-271938	11-1988	Japan (w/ abstract)		xx	
	AQ						
	AR						
	AS						
	AT						
	AU						
	AV						
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)							
<i>MK</i>	AW	S. Nelson: Using an ozone water last cleaning process to research the effects of process parameters on water contamination; SPWCC, pp. 230-242, March 4-7, 1996					
	AX	M. Hiroshi et al.: Dissolved-Gas Controlled Ultrapure Water Production System for Wet Cleaning Processes; The seventh International symposium on semiconductor manufacturing, proceedings of ISSM '98, Tokyo, pp. 428-431 (1998)					
	AY	M. Hiroshi et al.: Advanced UCT Cleaning Process Based on Specific Gases Dissolved Ultrapure Water; The eighth International symposium on semiconductor manufacturing, proceedings of ISSM '99 Tokyo, pp. 453-456 (1999)					
<i>MK</i>	AZ	M. Hiroshi et al.: Development of ozonated ultra-pure water supplying system using direct-dissolving method, SPWCC, pp. 51-60, March 13-16, 2000				<input checked="" type="checkbox"/> Additional References sheet(s) attached	
Examiner <i>[Signature]</i>				Date Considered <i>01/07/05</i>			
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

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N/K	AAA	T. Ohmi et al.: Native oxide growth and organic impurity removal on Si surface with ozone injected ultrapure water, J. Electrochem. Soc., 140(3), 804-810, 1993					
N/K	AAB	Werner Kern. Handbook of Semiconductor Cleaning Technology, 1993, Noyes Publications, Page 120.					
	AAC						
	AAD						
	AAE						
	AAF						
	AAG						
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	AAJ						
	AAK						
	AAL						
	AAM						
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	AAO						
	AAP						
	AAQ						
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